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A novel trench capacitor enhancement approach by selective liquid-phase deposition

S.-J. Lin | Chao-Sung Lai | Shian-Hau Liao | Chung-Yuan Lee | P.-I. Lee | Shi-Ming Chiang | Muh-Wang Liang
IEEE Transactions on Semiconductor Manufacturing
Year: 2005 | Volume: 18 | Issue: 4

☐ **A novel trench capacitor enhancement approach by selective liquid-phase deposition**
S.-J. Lin ; Chao-Sung Lai; Shian-Hau Liao; Chung-Yuan Lee; P.-I. Lee ; Shi-Ming Chiang; Muh-Wang Liang
IEEE Transactions on Semiconductor Manufacturing
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Abstract (1280 Kb)

High density and fully compatible embedded DRAM cell with 45nm CMOS technology (CMOS6)

T. Sanuki | Y. Sogo | A. Oishi | Y. Okayama | R. Hasumi | Y. Morimasa | T. Kinoshita | T. Komoda | H. Tanaka | K. Hiyama | T. Komoguchi | T. Matsumoto | K. Oota | T. Yokoyama | K. Fukasaku | R. Katsumata | M. Kido | M. Tamura | Y. Takegawa | H. Yoshimura | K. Kasai | K. Ohno | M. Saito | H. Aochi | M. Iwai | N. Nagashima | F. Matsuoka | Y. Okamoto | T. Noguchi
Digest of Technical Papers. 2005 Symposium on VLSI Technology, 2005.
Year: 2005

☐ **High density and fully compatible embedded DRAM cell with 45nm CMOS technology (CMOS6)**
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